

# PATENT ABSTRACTS OF JAPAN

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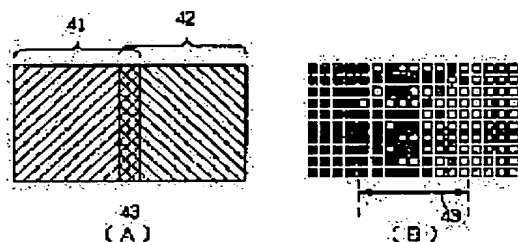
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## (54) PHOTOMASK AND EXPOSING METHOD

### (57)Abstract:

PURPOSE: To hardly perceive contrast difference caused on a connecting part in the case of performing exposure by picture synthesis.

CONSTITUTION: The connecting parts 43 obtained in the case of performing exposure by the picture synthesis are exposed to be overlapped to each other's, and unit patterns arrayed on the connecting part 43 are discretely, irregularly, and selectively exposed so that the unit patterns may not be repeatedly exposed twice or more. Thus, even through the contrast difference exists between the unit patterns formed on the connecting part, the unit patterns having the contrast difference are mixed, so that the connecting part is hardly perceived.



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